ABSTRACT OF THE DISCLOSURE

A manufacturing method for an optical waveguide device. The manufacturing method includes the steps of forming an optical waveguide in a substrate having an electro-optic effect, forming an SiO_2 film on the substrate, forming Si films on the SiO_2 film, the lower surface of the substrate, and at least a part of the side surface of the substrate to thereby make a conduction between the Si film formed on the SiO_2 film and the Si film formed on the lower surface of the substrate. The manufacturing method further includes the steps of applying a photoresist to the Si film formed on the SiO_2 film, patterning the photoresist so that a portion of the photoresist corresponding to the optical waveguide is left, forming a groove on the substrate along the optical waveguide by reactive ion etching, and removing the photoresist and the Si films.